

# Search Notes



Application No.

10/720,851

Examiner

Stephen W. Smoot

Applicant(s)

UESAWA, FUMIKATSU

Art Unit

2813

## SEARCHED

Class	Subclass	Date	Examiner
438	620	6/25/2004	SWS
438	637	6/25/2004	SWS
438	640	6/25/2004	SWS
438	669	6/25/2004	SWS
438	671	6/25/2004	SWS
438	673	6/25/2004	SWS
438	780	6/25/2004	SWS
Updated	Above	12/6/2004	SWS
438	978	12/6/2004	SWS
Updated	Above	3/2/2005	SWS
Updated	Above	6/8/2005	SWS

## INTERFERENCE SEARCHED

Class	Subclass	Date	Examiner
Same as Above		6/8/2005	SWS

## SEARCH NOTES (INCLUDING SEARCH STRATEGY)

	DATE	EXMR
Key Words: Mask - Organic, Tapered, Photoresist, Resist, Aperture, Hole Opening;	6/25/2004	SWS
Dual Hard Mask; Low Temperature Etching.	6/25/2004	SWS
Updated Above Search	12/6/2004	SWS
Updated Above Search	3/2/2005	SWS
Updated Above Search	6/8/2005	SWS
Search Tools - EAST (attached): USPAT; US PG PUBS; Derwent; EPO; JPO; IBM TDB	6/25/2004; 12-6-04;	SWS
	3-2-05; 8 6-8-05	SWS